



Volunteering Assignment in Webuye, Western Kenya.

SCN Partner organization: GAASPP

Help to Develop a Daycare Facility Model for Children of Teen Mothers

Duration: ca. 4 weeks onsite, full-time

Period: now - end of 2026

Location: GAASPP, Webuye, Kenya

Website of our SCN partner in Kenya:

GaasppKenya or <https://www.gaasppkenya.org/>

GAASPP runs an own guesthouse with an ecovillage, dining hall, ca. 100 rooms and a public swimming pool.





Objective

Establish operational standards and service delivery systems for a daycare facility supporting teen mothers' reintegration.

Scope of Expert Support

Facilitate operational workflow design

Guidance for Early Childhood Development standards

Conduct staff training on framework

Design child safeguarding and safety policy

Sustainability and cost modeling

Expected Deliverables

Daycare operational manual

Staff training completion

Child safeguarding framework

Sustainability model

Target Beneficiaries

Children and teen mothers and communities in Western Kenya

Your contributions/materials might be reused in several locations of the SCN Kenya where we work with teenage mothers and children and have impact even beyond Kenya in our partner NGOs.

Local Implementation Capacity

During your onsite stay GAASPP commits to:

- Local logistics & coordination
- Dedicated staff collaboration
- Community mobilization
- Safe accommodation and 24/7 availability

Your contribution: flights + local costs for accommodation & food

Volunteer Profile

- Early Childhood Development experience (0–5 yrs)
- Daycare/childcare operations design
- Child safeguarding & protection
- Staff training & capacity building
- Basic project management

Highly valuable:

- Cost-effective/scalable model design
- Low-resource/humanitarian experience
- Trauma-informed care
- Knowledge of teen mother reintegration programs

Interested?

Contact us via the SCN website at:

<https://scn-kenya.org/contact-us/>

The next steps:

- Review of your email/application
- Call introduction from SCN NGO leader and the applicant